

**AN IMPRINT LITHOGRAPHY TEMPLATE HAVING A
MOLD TO COMPENSATE FOR MATERIAL CHANGES OF
AN UNDERLYING LIQUID**

ABSTRACT OF THE DISCLOSURE

[0176] The present invention includes a template to form a recorded pattern on a substrate from a conformable material disposed between the template and the substrate, with the recorded pattern having recorded features with designed dimensions, the template comprising an original pattern having original features with original dimensions, with the original dimensions differing from the designed dimensions sufficient to compensate for volumetric changes of the conformable material that occurs upon the conformable material transitioning between first and second states.